

High Purity
SPUTTERING

TARGET

C

CARBON

SPUTTERING TARGET

Carbon sputtering targets are used for thin film deposition, typically for fuel cell, decoration, semiconductor, display, LED and photovoltaic devices, glass coating, etc. The applications for carbon are many and include its use as an alloying element with iron in the manufacture of steel, its use as brushes in electrical generators and motors, the use of colloidal graphite or carbon to coat surfaces (e.g. glass), in electrical assemblies to absorb microwaves and inhibit photoelectrons and secondary electrons, and the use of high purity carbon (graphite) in nuclear reactors to moderate neutrons.

Quick Facts

Product	:	Carbon Sputtering Target
Stock No	:	NS6130-10-1150
CAS	:	7440-44-0
Backing Plate	:	(As per Customer requirement)

Additional Characteristics

Stock No.	Purity	Diameter	Thickness
NS6130-10-1150	99.99%	50.8 mm \pm 1mm	3 mm \pm 0.5mm

Technical Specification

Molecular Formula	Molecular Weight	Melting Point
C	12.01g/mol	3652-3697°C



Follow us:



| www.nanoshel.com | sales@nanoshel.com

INTELLIGENT MATERIALS PVT LTD

Derabassi
Punjab (140507)
INDIA

+91 9779 550077, 9779238252

NANOSHEL UK LIMITED

Chapel House,
Chapel St Cheshire,
CW12 4AB United Kingdom

+44 (0) 74 105 488, +44 203 137 5187

NANOSHEL LLC

3422 Old Capitol Suit
1305 Wilmington DE - 19808
United States

+1 646 470 4911



20ZICE4589C



19ZAZGO1274G



20ZICE4588M

ISO 9001:2015
CERTIFIED COMPANY